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APPLICATION NO.	FI	LING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/911,855	09/911,855 07/23/200		Shoji Nakamura	04558/053001	3890
22511	7590	06/30/2005		EXAMINER	
OSHA LIA		•	RHEE, JANE J		
1221 MCKINNEY STREET SUITE 2800				ART UNIT	PAPER NUMBER
HOUSTON, TX 77010				1745	

DATE MAILED: 06/30/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	6 N					
	Application No.	Applicant(s)				
Office Action Cumment	09/911,855	NAKAMURA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Jane Rhee	1745				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply if NO period for reply is specified above, the maximum statutory period who is period for reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	6(a). In no event, however, may a reply be tim within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONEI	ely filed will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 09 Ma	ay 200 <u>5</u> .					
2a) ☐ This action is FINAL . 2b) ☑ This	action is non-final.					
3) Since this application is in condition for allowan						
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	3 O.G. 213.				
Disposition of Claims		,				
4) ☐ Claim(s) 1-8 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-8 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or						
Application Papers						
9) The specification is objected to by the Examiner	•					
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction 11) The oath or declaration is objected to by the Example 11.		• • • • • • • • • • • • • • • • • • • •				
Priority under 35 U.S.C. § 119	and the analysis of the	7.63.67.67.67.77.7.6				
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priori application from the International Bureau * See the attached detailed Office action for a list of	have been received. have been received in Application ty documents have been receive (PCT Rule 17.2(a)).	on No d in this National Stage				
Attachment(s)						
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)						
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail Da 5) ☐ Notice of Informal Pa 6) ☐ Other:	te atent Application (PTO-152)				
S. Patent and Trademark Office						

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 5/9/2005 has been entered.

Rejections Repeated

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-5 and 8 are rejected under 35 U.S.C. 102(e) as being anticipated by Takahashi et al. (6537648).

Takahashi et al. discloses a molded glass substrate for a magnetic disk (col. 11 line 22-24, col. 9 line 28) comprising upper and lower principal surfaces and an outer surface joining the upper and lower principal surfaces (col. 14 line 35-37), an inner surface defining a hole in a central portion of the substrate (col. 14 line 63-64), and with

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an outer diameter of 66mm and a thickness of 1mm (col. 14 line 38-39). Takahashi et al. discloses that the upper and lower surfaces have a small waviness of 0.398nm (col. 19 line 59). Takahasi et al. discloses that the principal surfaces have an average surface roughness Ra of 0.3nm (col. 8 line 67), and a maximum height Ry or Rmax of less than 5nm (col. 8 line 67). Takahasi et al. discloses that each of the principal surfaces have a flatness of 3 micrometers (col. 15 line 12).

As to the limitation of the outer surface having a molding free face and wherein the mirror surface property of a molding die is transcribed onto the upper and lower principal surfaces are product by process limitations. Process limitations are given little or no patentable weight. The method of forming the product is not germane to the issue of patentability of the product itself. Further, when the prior art discloses a product which reasonably appears to be either identical with or only slightly different than a product claim in a product-by-process claim, the burden is on the Applicant to present evidence from which the Examiner could reasonably conclude that the claimed product differs in kind from those of the prior art. In re Brown, 459 F.2d 531, 173 USPQ 685 (CCPA 1972); In re Fessman, 489 F.2d 742, 180 USPQ 324 (CCPA 1974). This burden is NOT discharged solely because the product was derived from a process not known to the prior art. In re Fessman, 489 F.2d 742, 180 USPQ 324 (CCPA 1974). Furthermore, the determination of patentability for a product-by-process claim is based on the product itself and not on the method of production. If the product in the product-by-process claim is the same or obvious from a product of the prior art, the claim is unpatentable even though the prior product was made by a different process. In re Thorpe, 227

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USPQ 946, 966 (Fed. Cir. 1985) and MPEP §2113. In this case, the limitations; wherein a mirror surface property of molding die is transcribed onto the upper and lower principal surfaces, and an outer diameter satisfies a desired dimensional tolerance by selecting a predetermined volume of a glass material, wherein a thickness of the molded glass substrate satisfies a desired dimension and tolerance by adjusting a barrel die size, or limitations like molded, molding free face, formed by molding between precision planar processing members, is a method of production and therefore does not determine the patentability of the product itself.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 6-7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takahashi et al. in view of Donley et al. (3660061).

Takahashi et al. discloses the glass substrate described above. Takahasi et al. fail to disclose that the inner surface is ground and polished or fire polished. Donley et al. teaches that fire polished glass surface is stronger than a ground and polished surface of plate glass and in addition the article is less subject to breakage on continuous exposure to hot sunlight than an article of similar appearance that is formed of a homogenous colored glass (col. 7 lines 64-67).

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Therefore, it would have been obvious to one having ordinary skill in the art at the time applicant's invention was made to provide Takahashi et al. with the inner surface that is ground and polished since Donely et al. teaches that it is a notoriously well known method for glass substrates as disclosed in col. 7 line 65 to give the glass the appearance of a colored glass composition to the human eye.

Furthermore, it would have been obvious to one having ordinary skill in the art at the time applicant's invention was made to provide Takahasi et al. with the inner surface that is fire polished because it is a stronger surface than a ground and polished surface of plate glass (col. 7 line 65).

Response to Arguments

4. Applicant's arguments filed 4/7/2005 have been fully considered but they are not persuasive.

In response to applicant's argument that Takahasi et al. fail to disclose that the outer surface is a molding free face, a molding free face is a product by process limitation, process limitations are given little or no patentable weight. The method of forming the product is not germane to the issue of patentability of the product itself. Further, when the prior art discloses a product which reasonably appears to be either identical with or only slightly different than a product claim in a product-by-process could reasonably conclude that the claimed product differs in kind from those of the claim, the burden is on the Applicant to present evidence from which the Examiner could reasonably conclude that the claimed product differs in kind from those of the prior art.

Conclusion

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jane Rhee whose telephone number is 571-272-1499. The examiner can normally be reached on M-F 9-6.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Patrick Ryan can be reached on 571-272-1292. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Jane Rhee June 27,2005

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PATRICK JOSEPH RYAN SUPERVISORY PATENT EXAMINER